13. An integrated method for the fabrication of nanostructures.

REMARKS - General

By the above amendments, applicants have rewritten or cancelled their specification and claims to define the invention more particularly and distinctly.

The Restriction Of Claims For Examination Under 35 U.S.C. § 121

The last O.A. required restriction to one of the following inventions under 35 U.S.C. § 121:

- I. Claims 1-6, drawn to a method, classified in class 264, subclass 656.
- II. Claim 7, drawn to a product, classified in class 501, subclass 85.

Accordingly, applicants have elected Group I and withdrawn claim 7.

Amendments To Specification and Claims To Overcome Paradox

The above requested modifications to the specification and to previous claim 1(f) all consist of replacing the wording "at least" with "at most". These modifications are necessary in order to relieve an inconsistency.

The paradox becomes apparent when considering applicants' statement on page 20, lines 13-15 of the specification, viz.

"Further studies have also shown that it is not necessary to coat the entire surface of the nanoparticles with a monolayer of surfactant. When only 50% of the surface receives a monolayer of surfactant Φ_m already reaches a maximum."

Consequently, the use of the term "at least" on page 17, line 10 and on page 20 line 19 of the specification and in previous claim 1(f) results in an incongruity since it would not make sense, giving the conclusion of said studies, to coat at least 50% of the surface with a monolayer of surfactant when above statement clearly indicates that this would be ineffective and equate to wastage of surfactant.

Accordingly, the use of the term "at least" in the Specification and Claims was made purely by inadvertence when in fact the term "at most" was at all times intended. Applicants apologize for this error.

Conclusion

For all of the above reasons, applicants submit that the specification and claims are now in proper form.

Conditional Request For Constructive Assistance

Applicants have amended the specification and claims of this application so that they are proper and definite. If, for any reason this application is not believed to be in full condition for allowance, applicants respectfully request the constructive assistance of the Examiner pursuant to M.P.E.P. § 2173.02 and § 707.07(j) in order that the undersigned can place this application in allowable condition as soon as possible and without the need for further proceedings.

Very respectfully,

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with the Malaysian Postal	ertify that on the date below this document will be deposited Services as Express Airmail in an envelope addressed to MENTS, ASSISTANT COMMISSIONER FOR PATENTS USA."
October 14, 2002	Sulls
	Romain L. Billiet, Applicant